(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization International Bureau



T LODIE BUSSEDI IN SOLUB ALKA DOMIN BOMI BILLI IN HA BOMI KUSA DINDA ALKA KUSA KUSA KUSA KUSA KUSA KUSA KUSA K

(43) International Publication Date 1 July 2004 (01.07.2004)

PCT

(10) International Publication Number WO 2004/055873 A1

(51) International Patent Classification⁷:

.

H01L 21/20

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(21) International Application Number:

PCT/KR2002/002361

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(22) International Filing Date:

14 December 2002 (14.12.2002)

(81) Designated States (national): CN, JP, KR, US.

(25) Filing Language:

Korean

(84) Designated States (regional): European patent (AT, BE,

(26) Publication Language:

English

BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, SI, SK, TR).

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Published:

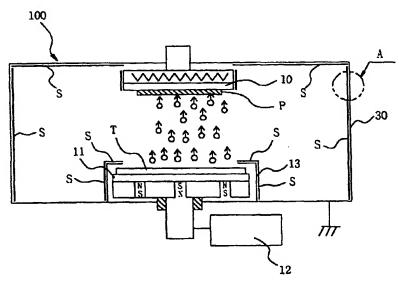
with international search report

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For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: THIN FILM FORMING APPARATUS



(57) Abstract: The present invention relates to a thin forming apparatus, i.e. an apparatus for forming thin films of various materials on substrates, for example, in processes of fabricating semiconductor wafers or liquid crystal displays (LCDs). The thin film forming apparatus comprises a substrate support for mounting a substrate on which a thin film is to be formed, and a chamber that encloses the substrate support and has proper operation conditions. Then, adsorption means constructed by applying a ductile metal material such as indium, tin, lead or antimony on a metal or synthetic resin base material are attached to surfaces of components within the thin film forming apparatus except the substrate. Accordingly, it is possible to fundamentally prevent failure of formation of a thin film due to adhesion of a portion of an unnecessary thin film, which has been formed on and then peeled off from the surfaces of the components, to the substrate.

